



Behaviour of sheath in electronegative warm plasma

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Abstract

Behaviour of sheath formed on two types of probes, namely cylindrical and spherical probes, has been investigated in terms of its thickness, in front of the conducting probes immersed in an electronegative plasma for different negative to positive ion mass ratios, by considering three electronegative gases, i.e. CF_4 , O_2 and C_{60} . Contrary to others' work, complete fluid equations are written for negative ions also in addition to those of positive ions considering their different masses. Increasing negative to positive ion mass ratio is found to result in an increment of the sheath thickness. The magnitude of the sheath thickness is enhanced with an increment in the positive ions' temperature, whereas the magnitude of the sheath thickness is reduced with increased negative ions' temperature and background density of the negative ions. The analysis of the case of a large probe radius, used in the surface-nitriding process, for both the geometries is attended. Additionally, the comparison between the results for electropositive plasma and electronegative plasma and for behaviour of negative ions with their Boltzmann distribution and fluid approach has also been attempted herewith and a noteworthy difference is realized. The case of doubly charged ions is also entertained herewith.

Keywords Electronegative plasma · Mass ratio · Sheath thickness · Ion temperature · Doubly charged ions

Introduction

Electronegative plasmas are of enormous interest due to their expanding applications in many fields, like deposition of thin films [1–4], sterilization process [5], plasma–surface interaction [6–10], semiconductor industries [11], microelectronics industries [12], etc., where plasma containing both positive and negative ions is preferable. In many applications, they serve as ion source because of the requirement of both positive and negative ion beams; these have also been used in low-energy beam applications and also when energetic electrons can produce destructive effects on the surface [13]. Therefore, the temperature of the ions deposited on the surface of the material under investigation is essential to take care of, as it can lead to significant changes in the surface properties. The best method to ward off irregular shapes is the addition of negative ions to counterbalance the positive ions, assemble on the wafer and also to enhance the

working of materials using in the fabrication of integrated circuits. Electronegative plasmas are widely adopted for soft substrates to have a defect-free analysis, as they develop immensely small sheath voltage in comparison with electropositive one.

The immersion of a metallic probe in a plasma containing electrons, positive ions and negative ions results in a non-neutrality region surrounding it, termed as the sheath. The theoretical study of the sheath formation is useful in surface hardening process like plasma immersion ion implantation [14], in mass spectroscopy [15] where analysis of the formation of the sheath at spectrometer entrance window is required for the correct interpretations of the results. Probe analysis permits us to measure the useful quantities like potential profile, density distributions of plasma species, electric field profile, sheath thickness, etc. On the other hand, by characterizing the dust grain as a conducting spherical probe in plasma, one can determine the potential with the help of probe theories [16, 17]. The usefulness of probe theories also lies in the inspection of the nature of plasma surrounding a satellite in outer space. Many authors have observed the noteworthy influence on the characteristics of the probe in the cases of low-frequency sheath processes [18–20]. Also, X-ray emission has been observed

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when laser light is launched on tin slab forming a sheath of ions which radiate [21–23].

Due to the presence of second negative species, i.e. negative ions, the plasma parameters are of a distinctive nature [24, 25]. In this paper, we deal with three electronegative gases: one which contains halogen, i.e. fluorocarbon (CF₄) [26], and other two gases, those do not contain halogen, are oxygen plasma [27] and C₆₀ plasma [28, 29]. Such electronegative gases are adopted because of their ability to produce high negative ion density compared to that of the electrons. The difference between the mobilities of two types of the ions is not high, so these must be examined by similar treatment as opposed to the others' work [30–35] where Maxwellian approximation (Boltzmann distribution) is considered for negative ions and the mass of negative ions is neglected. The negative ions also should be described by the fluid equations as in the case of positive ions to study a realistic situation. Unlike others, we also consider the drift term in the momentum transfer equation of negative ions to explore the practical case by taking into account the generalized situation of their different masses from the positive ions. In the present work, we investigate the sheath thickness profile as a function of the temperatures of positive and negative ions, electronegativity and negative to positive ion mass ratios. The studies are conducted for two cylindrical and spherical geometries, i.e. when cylindrical and spherical probes are immersed in the plasma and sheath is formed on them. A comparative study of the sheath thickness profile for the negative ions' behaviour by Boltzmann distribution and fluid approach is also entertained herewith to validate the choice of fluid approach for negative ions also.

Basic equations

To reveal the sheath structure formed surrounding the cylindrical and spherical probes, we consider a collision-less, unmagnetized and warm electronegative plasma, where the continuity and momentum transfer equations describe the behaviour of positive and negative ions. Poisson's equation reveals the dependency of a potential profile on various factors, like temperature, mass ratio, density, etc. These equations are written as follows:

$$\frac{1}{r^K} \frac{d}{dr} (r^K n_P v_P) = 0, \quad (1a)$$

$$\frac{1}{r^K} \frac{d}{dr} (r^K n_N v_N) = 0, \quad (1b)$$

$$M_P v_P n_P \frac{dv_P}{dr} = Z_P n_P e \vec{E} - \vec{\nabla} P_P, \quad (2a)$$

$$M_N v_N n_N \frac{dv_N}{dr} = -Z_N n_N e \vec{E} - \vec{\nabla} P_N, \quad (2b)$$

$$\frac{d^2 \varphi}{dr^2} + \frac{K}{r} \frac{d\varphi}{dr} = -\frac{e}{\epsilon_0} (Z_P n_P - Z_N n_N - n_e). \quad (3)$$

We consider that the behaviour of electrons is governed by their usual Boltzmann distribution. Hence,

$$n_e = n_{e0} \exp\left(\frac{e\varphi}{k_B T_e}\right) \quad (4)$$

In these equations, M_P and M_N are masses, v_P and v_N are velocities, n_P and n_N are densities, and Z_P and Z_N are charges of positive and negative ions, respectively. K designates the geometry of probe, with values 1 and 2 for the cylindrical and spherical geometries, respectively. n_{e0} is the background electron density in plasma. φ is the electric potential, which is a function of distance r from the position of the probe. With respect to plasma, the probe is considered to be at the negative potential. P_P and P_N are the pressure gradient terms for positive and negative ions, respectively, defined as:

$$P_P = \frac{K_B \gamma_P}{n_{P0}^{C-1}} n_P^C, \quad (5a)$$

$$P_N = \frac{K_B \gamma_N}{n_{N0}^{C-1}} n_N^C. \quad (5b)$$

where γ_P and γ_N are the temperatures, and n_{P0} and n_{N0} are the background densities of positive and negative ions, respectively. C is polytropic constant with value 3 for large probe radius for both the geometries.

When these results are introduced in Eqs. (2a) and (2b), the resulting equations appear as:

$$M_P v_P \frac{dv_P}{dr} + Z_P e \frac{d\varphi}{dr} + \frac{CK_B \gamma_P n_P^{C-2}}{n_{P0}^{C-1}} \frac{dn_P}{dr} = 0, \quad (6a)$$

$$M_N v_N \frac{dv_N}{dr} - Z_N e \frac{d\varphi}{dr} + \frac{CK_B \gamma_N n_N^{C-2}}{n_{N0}^{C-1}} \frac{dn_N}{dr} = 0. \quad (6b)$$

Quasi-neutrality condition is stated as follows:

$$Z_P n_{P0} \cong Z_N n_{N0} + n_{e0} \quad (7)$$

To carry out the equations in dimensionless form, we normalized them with suitable normalization parameters, defined as follows:

$$x = \frac{r}{\lambda_d}, y = -\frac{e\phi}{k_B T_e}, N_P = \frac{n_P}{n_{e0}}, N_N = \frac{n_N}{n_{e0}},$$

$$N_e = \frac{n_e}{n_{e0}}, \chi_P = \left(\frac{v_P}{v_{P0}}\right)^2, \chi_N = \left(\frac{v_N}{v_{N0}}\right)^2.$$

where v_{P0} and λ_d are, respectively, the ion-acoustic speed and Debye length, described as:

$$\lambda_d = \sqrt{\frac{\epsilon_0 K_B T_e}{n_{e0} e^2}}, v_{P0} = \sqrt{\frac{2K_B T_e}{M_P}}.$$

After normalization, the above equations will appear as:

$$\frac{1}{x^K} \frac{d}{dx} \left(x^K N_P \chi_P^{\frac{1}{2}} \right) = 0, \tag{8a}$$

$$\frac{1}{x^K} \frac{d}{dx} \left(x^K N_N \chi_N^{\frac{1}{2}} \right) = 0, \tag{8b}$$

$$2\sqrt{\chi_P} \frac{d}{dx} \sqrt{\chi_P} - Z_P \frac{dy}{dx} + \frac{CT_P N_P^{C-2}}{N_{P0}^{C-1}} \frac{dN_P}{dx} = 0, \tag{9a}$$

$$2\frac{M_N}{M_P} \sqrt{\chi_N} \frac{d}{dx} \sqrt{\chi_N} + Z_N \frac{dy}{dx} + \frac{CT_N N_N^{C-2}}{N_{N0}^{C-1}} \frac{dN_N}{dx} = 0, \tag{9b}$$

$$\frac{d^2 y}{dx^2} + \frac{K}{x} \frac{dy}{dx} = (Z_P N_P - Z_N N_N - N_e), \tag{10}$$

$$N_e = \exp(-y), \tag{11}$$

$$Z_P N_{P0} = Z_N N_{N0} + N_{e0}. \tag{12}$$

Here, we defined $T_P = \frac{y_P}{T_e}$ and $T_N = \frac{y_N}{T_e}$ as the temperature ratio of the positive ions and negative ions, respectively, to electrons. $N_{P0} = \frac{n_{P0}}{n_{e0}}$ and $N_{N0} = \frac{n_{N0}}{n_{e0}}$ are defined as background density ratios of the positive ions and negative ions, respectively, to the electrons. N_{P0} and N_{N0} are, respectively, designated as electropositivity and electronegativity of the plasma.

Normalized positive and negative ion current (i_P and i_N) collected at the probe surface can be described as:

$$i_P = \frac{I_P}{x_P^{2-K}} = \frac{Z_P N_P \sqrt{\chi_P} x^K}{x_P^{2-K}} \tag{13a}$$

$$i_N = \frac{I_N}{x_P^{2-K}} = -\frac{Z_N N_N \sqrt{\chi_N} x^K}{x_P^{2-K}} \tag{13b}$$

Here, x_P corresponds to the probe radii. Integrating Eqs. (8a) to (9b) and using quasi-neutrality condition at the plasma, we will get:

$$x^K N_P \chi_P^{\frac{1}{2}} = \text{constant} = \frac{i_P}{Z_P} \tag{14a}$$

$$x^K N_N \chi_N^{\frac{1}{2}} = \text{constant} = -\frac{i_N}{Z_N} \tag{14b}$$

$$\frac{C\gamma_P}{C-1} \left(\frac{Z_P}{1+Z_N N_{N0}} \right)^{C-1} N_P^{C+1} - \left(Z_P y + \frac{CT_P}{C-1} \right) N_P^2 + \frac{i_P^2}{x^{2K} Z_P^2} = 0 \tag{15a}$$

$$\frac{C\gamma_N}{C-1} \left(\frac{1}{N_{N0}} \right)^{C-1} N_N^{C+1} + \left(Z_N y - \frac{CT_N}{C-1} \right) N_N^2 + \frac{M_N}{M_P} \frac{i_N^2}{x^{2K} Z_N^2} = 0 \tag{15b}$$

On solving Eqs. (15a) and (15b), the density profiles of positive and negative ions, respectively, will be obtained for appropriate parameters. For $C=3$, Eqs. (15a) and (15b) turn out to be

$$a_P N_P^4 - b_P N_P^2 + c_P = 0 \tag{15a'}$$

$$a_N N_N^4 + b_N N_N^2 + c_N = 0 \tag{15b'}$$

where $a_P = \frac{3T_P}{2} \left(\frac{Z_P}{1+Z_N N_{N0}} \right)^2$, $b_P = \left(Z_P y + \frac{3T_P}{2} \right)$, $c_P = \frac{i_P^2}{x^{2K} Z_P^2}$, $a_N = \frac{3T_N}{2} \left(\frac{1}{N_{N0}} \right)^2$, $b_N = \left(Z_N y - \frac{3T_N}{2} \right)$ and $c_N = \frac{M_N}{M_P} \frac{i_N^2}{x^{2K} Z_N^2}$.

Solutions of Eqs. (15a') and (15b') are obtained as:

$$N_P = \pm \sqrt{\frac{b_P \pm \sqrt{b_P^2 - 4a_P c_P}}{2a_P}}, N_N = \pm \sqrt{\frac{-b_N \pm \sqrt{b_N^2 - 4a_N c_N}}{2a_N}}$$

For $C=3$, i.e. for large probe radius, these equations have four roots: two positive and two negative. Later roots are neglected, as the charged particle density cannot be negative, whereas, from positive roots, one which gives higher charge density at the sheath edge is adopted to have a significant number of ions to form the sheath and is given as follows:

$$N_P = \sqrt{\frac{b_P + \sqrt{b_P^2 - 4a_P c_P}}{2a_P}}, N_N = \sqrt{\frac{-b_N + \sqrt{b_N^2 - 4a_N c_N}}{2a_N}} \tag{16}$$

After substituting the charge particle density value in Eq. (10), one can examine the behaviour of potential surrounding the probe for different parameters like temperature, density, mass ratio, etc. The term mass ratio is appearing in Eq. (15b), in turn, will appear in the final solution of Poisson's equation and reports its dependency on various

parameters and consequently will modify the behaviour significantly. Using Eqs. (11) and (16), the final form of the Poisson's equation appears as:

$$\frac{d^2y}{dx^2} + \frac{K}{x} \frac{dy}{dx} = \left(Z_P \sqrt{\frac{b_P + \sqrt{b_P^2 - 4a_P c_P}}{2a_P}} - Z_N \sqrt{\frac{-b_N + \sqrt{b_N^2 - 4a_N c_N}}{2a_N}} - \exp(-y) \right) \quad (17)$$

To solve this equation, we must enumerate the two boundary conditions. Hence, we define a point (x_S, y_S) near the sheath edge, where the condition of quasi-neutrality is still valid. Corresponding to this is the plasma solution given as:

$$Z_P \sqrt{\frac{b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}}}{2a_{PS}}} \cong Z_N \sqrt{\frac{-b_{NS} + \sqrt{b_{NS}^2 - 4a_{NS} c_{NS}}}{2a_{NS}}} + \exp(-y_S) \quad (18)$$

where a_{PS}, b_{PS}, c_{PS} and a_{NS}, b_{NS}, c_{NS} are defined above with the subscript 'S' that designates the charged particle density at point (x_S, y_S) , obtained by setting $x = x_S$ and $y = y_S$ in Eq. (16). Another boundary condition is calculated by differentiating Eq. (18). This is stated as:

$$\left(\frac{dy}{dx} \right)_{\text{at S}} = \left[\begin{aligned} & -\frac{\sqrt{2a_{NS} K M_N i_N^2}}{Z_N x_S^{2K+1} M_P} \left(-b_{NS} + \sqrt{b_{NS}^2 - 4a_{NS} c_{NS}} \right)^{-\frac{1}{2}} \left(b_{NS}^2 - 4a_{NS} c_{NS} \right)^{-\frac{1}{2}} \\ & + \frac{\sqrt{2a_{PS} K i_P^2}}{Z_P x_S^{2K+1}} \left(b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}} \right)^{-\frac{1}{2}} \left(b_{PS}^2 - 4a_{PS} c_{PS} \right)^{-\frac{1}{2}} \end{aligned} \right] \\ \times \left\{ \left[\frac{Z_N}{\sqrt{2a_{NS}}} \left(\frac{-b_{NS} + \sqrt{b_{NS}^2 - 4a_{NS} c_{NS}}}{2} \right)^{-\frac{1}{2}} \right] \left(-Z_N + Z_N b_{NS} \left(b_{NS}^2 - 4a_{NS} c_{NS} \right)^{-\frac{1}{2}} \right) \right. \\ \left. - \left[\frac{Z_P}{\sqrt{2a_{PS}}} \left(\frac{b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}}}{2} \right)^{-\frac{1}{2}} \right] \left(Z_P + Z_P b_{PS} \left(b_{PS}^2 - 4a_{PS} c_{PS} \right)^{-\frac{1}{2}} \right) - \exp(-y_S) \right\}^{-1} \quad (19)$$

Using these two boundary conditions [Eqs. (18)–(19)], we solve Poisson's equation numerically, defined in Eq. (17) for a particular set of parameters.

Results and discussion

Spherical geometry

For spherical geometry, geometric constant $K=2$ and polytropic constant $C=3$ are used. The behaviour of the electric potential is revealed by the Poisson's equation with

the help of two appropriate boundary conditions which are described above [Eqs. (18)–(19)]. We have assigned a constant magnitude of the electric potential at the probe/

wall surface (say $y_P \sim 100$) to determine the probe position, which in turn provided the information about the sheath thickness, i.e. $x_{PP} - x_S$. Here, x_{PP} and x_S correspond to the position of probe/wall and the sheath edge, respec-

tively. The sheath thickness profile as a function of T_P for different T_N is portrayed herewith in Fig. 1 and observed noteworthy modifications. The impact of positive ions' temperature on the sheath thickness is important to study while dealing with surface–plasma interaction problems.

This is because the temperature of positive ions imposed on the material surface may lead to significant modifications in its surface properties. The magnitude of the sheath thickness is enhanced with an increment in the T_P , whereas it is reduced with increased T_N . For lower T_P , the difference in the magnitude of the sheath thickness for different T_N is minuscule; however, with increasing T_P , a significant difference in the magnitude of the sheath thickness is appeared for different T_N . For fixed N_{N0} , the density of the negative ions near the sheath edge is increased with an increased T_N . Therefore, the point where the condition of quasi-neutrality starts to hold is moved towards

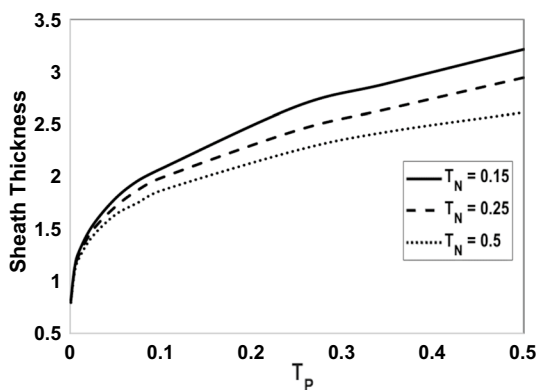


Fig. 1 Sheath thickness profile as a function of T_p for different T_N when $K=2$, $Z_p=1$, $Z_N=1$, $M_p=69$, $M_N=19$, $N_{N0}=2$, $y_p=100$ and $x_p=10$

the probe/wall surface, which in turn results in a smaller sheath thickness.

The sheath thickness profile as a function of N_{N0} for different $\frac{M_N}{M_p}$ is depicted in Fig. 2. We considered three electronegative plasmas: CF_4 , O_2 and C_{60} . The majority of the positive and negative ions found in these plasmas are CF_3^+ and F^- , O_2^+ and O^- , C_{60}^+ and C_{60}^- , respectively. For these plasmas, the mass ratio of negative to positive ion turns to be 0.275, 0.5 and 1, respectively. The analysis of the mass ratio of negative to positive ions is imperative as it leads to considerable modifications in the profiles of the plasma parameters which will benefit in experimental applications such as plasma nitriding. The magnitude of the sheath thickness is enhanced with an increment in the $\frac{M_N}{M_p}$, whereas it is reduced with increased N_{N0} . For fixed T_N , a greater number of negative ions are available near the sheath edge with an enhanced N_{N0} . Consequently, a smaller sheath thickness is depicted for higher N_{N0} .

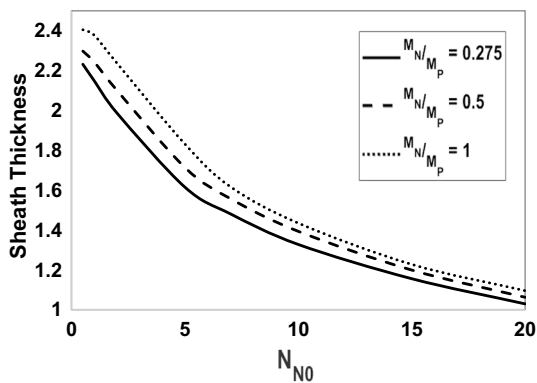


Fig. 2 Sheath thickness profile as a function of N_{N0} for different $\frac{M_N}{M_p}$ when $K=2$, $Z_p=1$, $Z_N=1$, $T_p=0.1$, $T_N=0.25$, $y_p=100$ and $x_p=10$

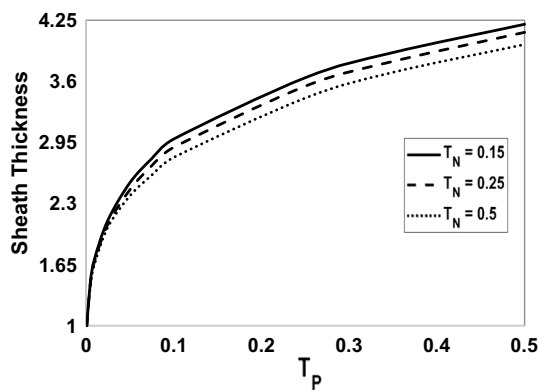


Fig. 3 Sheath thickness profile as a function of T_p for different T_N when $K=1$, $Z_p=1$, $Z_N=1$, $M_p=69$, $M_N=19$, $N_{N0}=2$, $y_p=100$ and $x_p=10$

Cylindrical geometry

For cylindrical geometry, geometry constant $K=1$ and polytropic constant $C=3$ are used. In Fig. 3, the magnitude of the sheath thickness as a function of T_p for different T_N is depicted. We found the magnitude of the sheath thickness to reduce with an increment in T_N , but to enhance with an increased T_p , consistent with the case of spherical geometry. However, for cylindrical geometry, the magnitude of the sheath thickness is relatively higher in comparison with the case of spherical geometry. In other words, for cylindrical geometry, shielding of the probe is not perfect; therefore, condition of quasi-neutrality occurs at a relatively larger distance from the probe/wall surface. The effect of positive (negative) ion temperatures on the sheath thickness remains the same in cylindrical geometry also, and the sheath thickness is increased (reduced) for higher temperature.

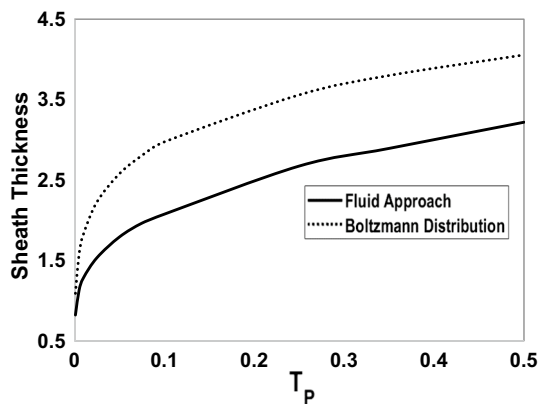


Fig. 4 Comparative study of sheath thickness profile for the behavior of negative ions by fluid approach and Boltzmann distribution as a function of T_p when $K=2$, $Z_p=1$, $Z_N=1$, $M_p=69$, $M_N=19$, $N_{N0}=2$, $y_p=100$ and $x_p=10$, $T_N=0.15$

Limiting cases

Boltzmann distributed negative ions

A comparative study of the profile of the sheath thickness for the behaviour of the negative ions by Boltzmann distribution and fluid approach is entertained herewith and depicted in Fig. 4. The sheath of higher thickness is formed when negative ions obeyed Boltzmann distribution for all T_p . On comparing these two cases, for lower T_p , the difference in the magnitude of the sheath thickness is miniature, whereas a significant difference is obtained with increasing T_p . This difference is occurred due to the negligence of the mass of the negative ions and their drift term also. From this figure, it is clearly shown that drift term of the negative ions has a significant effect on the system; therefore, it should not be neglected.

Electropositive plasma

The appropriate way to study the electropositive plasma using the same theoretical model is to omit out all the equations which described the behaviour of negative ions in the given system. In other words, we omit out the continuity and momentum transfer equation for the negative ions to investigate the sheath characteristics for a plasma without negative ions, i.e. for electropositive plasma. The resulting Poisson’s equation is stated as follows:

$$\frac{d^2y}{dx^2} + \frac{K}{x} \frac{dy}{dx} = \left(Z_p \sqrt{\frac{b_p + \sqrt{b_p^2 - 4a_p c_p}}{2a_p}} - \exp(-y) \right) \tag{20}$$

where $a_p = \frac{3T_p}{2} Z_p^2$, $b_p = \left(Z_p y + \frac{3T_p}{2} \right)$, and $c_p = \frac{i_p^2}{x^{2K} Z_p^2}$.

Corresponding to this [a point (x_s, y_s) near the sheath edge] is the plasma solution given as:

$$Z_p \sqrt{\frac{b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}}}{2a_{PS}}} \cong \exp(-y_s) \tag{21}$$

Another boundary condition is calculated by differentiating Eq. (21). This is stated as:

$$\left(\frac{dy}{dx} \right)_{at S} = \left[\frac{\sqrt{2a_{PS} K i_p^2}}{Z_p x_s^{2K+1}} \left(b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}} \right)^{-\frac{1}{2}} \left(b_{PS}^2 - 4a_{PS} c_{PS} \right)^{-\frac{1}{2}} \right] \times \left\{ - \left[\frac{Z_p}{\sqrt{2a_{PS}}} \left(\frac{b_{PS} + \sqrt{b_{PS}^2 - 4a_{PS} c_{PS}}}{2} \right)^{-\frac{1}{2}} \right] \left(Z_p + Z_p b_{PS} \left(b_{PS}^2 - 4a_{PS} c_{PS} \right)^{-\frac{1}{2}} \right) - \exp(-y_s) \right\}^{-1} \tag{22}$$

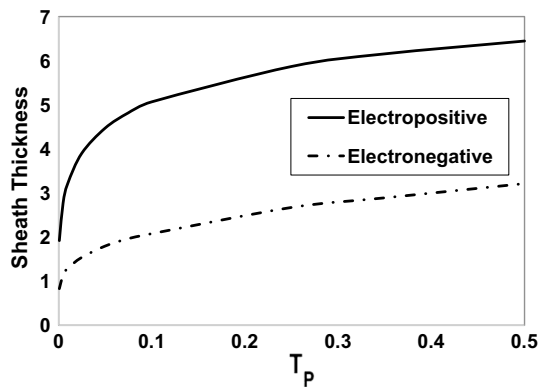


Fig. 5 Comparative study of sheath thickness profile as a function of T_p for electropositive and electronegative plasma when $K=2$, $Z_p=1$, $y_p=100$ and $x_p=10$ for electropositive plasma and $K=2$, $Z_p=1$, $Z_N=1$, $M_p=69$, $M_N=19$, $N_{N0}=2$, $T_N=0.15$, $y_p=100$ and $x_p=10$ for electronegative plasma

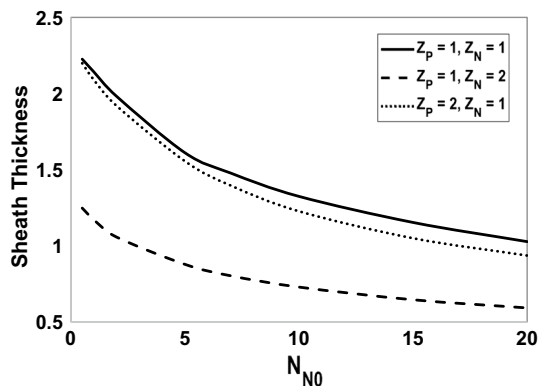


Fig. 6 Comparative study of sheath thickness profile as a function of N_{N0} for singly and doubly charged ions when $K=2$, $M_p=69$, $M_N=19$, $T_p=0.1$, $T_N=0.25$, $y_p=100$ and $x_p=10$

The comparative study of sheath thickness profile for electropositive and electronegative plasma is also entertained herewith and depicted in Fig. 5. The sheath thickness of higher magnitude is formed for electropositive plasmas for all cases of positive ions’ temperature. The difference in the magnitude of the sheath thickness for these two cases increases with increasing positive ions’ temperature.

Doubly charged ions

In most of the plasma systems, there is a finite concentration of the doubly charged ions. The concentration of such doubly charged ions depends upon the plasma parameters. The case of doubly charged ions in the plasma is investigated herewith and compared with the singly charged ions in Fig. 6. We have considered three cases: $Z_p = 1$ and $Z_N = 1$; $Z_p = 1$ and $Z_N = 2$; and $Z_p = 2$ and $Z_N = 1$. From Fig. 6, we have observed a significant modification in the magnitude of the sheath thickness when negative ions are doubly charged, whereas a minuscule modification in the magnitude of the sheath thickness is detected when positive ions are doubly charged.

The advantage of adopting spherical and cylindrical probes in the plasma processing is the production of large saturation current for the same density, which, in turn, plays a momentous advantage for measurements in the regions of very low density.

Conclusions

We studied the effect of negative to positive ion mass ratio for the very first time for different plasma conditions to understand the exact sheath behaviour. The magnitude of the sheath thickness is found to be larger when the mass ratio is larger, and the positive ions carry higher temperature, whereas negative ions carry lower temperature. Sheath behaviour is strongly depending on the electronegativity of the medium, and its thickness is reduced with an increment in the electronegativity. A comparative study of cylindrical and spherical probes yields that the sheath of higher magnitudes is formed in cylindrical case. Additionally, the results for fluid behaviour of negative ions are compared with Boltzmann distribution of negative ions to have a better understanding of the problem proposed here. It is depicted that the sheath of lower magnitude is resulted for the case of fluid approach. This difference is arisen due to the negligence of the drift term. This noteworthy difference between the two cases justified the worth consideration of the drift term of negative ions and the mass of the negative ions. These results shall play an imperative role in those experimental fields where the plasmas composed of negative ions are preferred and also where the temperature of ions has a considerable effect on the surface properties. The investigation of doubly charged ions is also conducted and observed a significant reduction in the magnitude of the sheath thickness when negative ions are doubly charged in comparison with singly charged negative ions.

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